

Abstract of the Disclosure

A gas supplying apparatus for atomic layer deposition, which generates a source gas by vaporizing a powder source and supplies the source gas into a reaction chamber of an atomic layer deposition apparatus, is provided. The apparatus includes a container containing the powder source, a cover, which is installed in an upper portion of the container and covers the container, a gas inlet tube, which supplies a carrier gas into the container and includes a preheating portion wound on an outer circumference of the container and a connection portion for connecting the preheating portion and a carrier gas storage tank, a gas outlet tube, which exhausts the source gas generated in the container together with the carrier gas, a heating unit heating the container and the preheating portion of the gas inlet tube together, a temperature sensor, which detects temperature in the container, and a temperature controller, which controls a power supply of the heating unit depending on a value of temperature detected by the temperature sensor.